

# BM 300

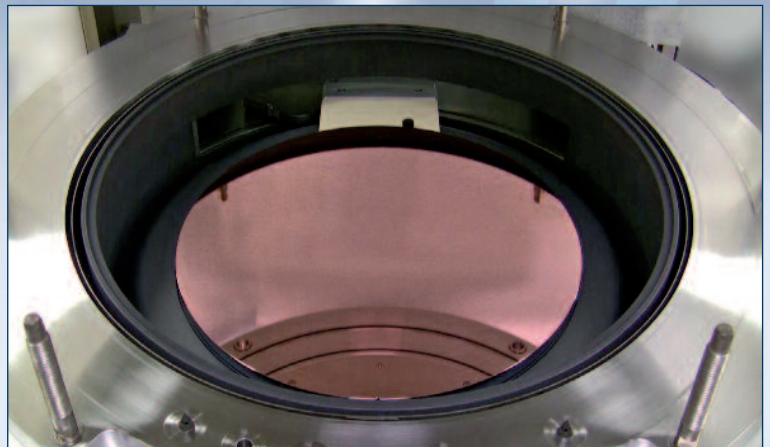
# AIXTRON



## 300 mm Wafer-scale Production of Carbon Nanotubes and Graphene

### Features

- 1050° C substrate heater
- Uniform gas delivery through showerhead
- Precise precursor concentration control
- Heater to showerhead gap adjust
- Wafer rotation during process
- ARGUS real-time wafer temperature mapping
- Optical ports at normal incidence to wafer



Advanced Heater Design for Outstanding Uniformity



BM 300 Process Module and Handler System



## Results

